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The poloidal cross section of the Ring Trap 1 (RT-1) device. A high-temperature superconducting coil levitated in the vacuum chamber generates a magnetospheric configuration. A variety of interesting phenomena are observed in the magnetosphere. Electrons injected from the edge confinement region are transported to the strong magnetic field region against the density gradient and stably trapped. The confinement time exceeds 300 s. (Haruhiko SAITOH *et al.*, Plasma and Fusion Research Vol.4, 054 (2009) <http://www.jspf.or.jp/PFR/>)